REMARKS

Claims 1-34 are cancelled. Claims 35-74 are added and are the only claims in the application.

Independent claim 35 includes all of the limitations, plus others, of the independent claim that was allowed in the parent application. The added limitations are supported by the specification as filed. Accordingly, allowance of claims 35-48 is warranted and requested.

Independent claims 49 and 58 recite that the outermost portion of the first layer is formed or deposited at a first temperature of at least 400°C. After depositing or otherwise forming the first layer, and without letting the outermost portion of the first layer cool from the first forming temperature to a temperature below 360°C, titanium in either elemental or alloy form is deposited onto the first layer and formed therefrom during such depositing is an alloy of titanium and the aluminum from the first layer. Support for the same is inherent from Applicant's application as filed.

The respective subject matter of independent claims 49 and 58 is not shown nor suggested by the previously applied art, for example Besser et al., Colgan et al. and Yoshikawa. For instance, the portion of Besser et al. relied upon by the Examiner in the parent application discloses at the bottom of column 3 a preheat step occurring to a temperature of at least 350°C after formation of the indicated aluminum or aluminum alloy layer. Accordingly, this reference inherently teaches substantial cooling of the outermost portion of the

aluminum or aluminum alloy layer after formation, as otherwise a heating step to approximately 350°C would not be necessary, and in any event does not suggest Applicant's independent claims 49 and 58 as presented.

Regarding Colgan et al., such clearly teaches an anneal subsequent to deposition to form TiAl₃, and accordingly, does not suggest doing so in the manner Applicant claims.

Similarly, the Yoshikawa reference depicts patterning of its subject aluminum layer 3 after formation and prior to deposition of a titanium film 4. Accordingly, inherent cooling of the Yoshikawa substrates occurs outside of the limits of Applicant's independent claims 49 and 58.

The claims of this application are believed to be in condition for allowance, and indicated action to that end is requested.

Respectfully submitted,

Dated: 2-16-0/

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